In response to the November 7, 2000 Office Action in this application, please amend the application as follows:

In the Claims

(Amended) A scrubbing process for the abatement of a gas component in a gas stream containing same, said scrubbing process comprising introducing the gas stream and a scrubbing liquid to a first gas/liquid contacting chamber and effecting gas/liquid contacting therein; flowing the effluent gas from the first contacting chamber to a second gas/liquid contacting chamber and introducing to said second contacting chamber a second scrubbing liquid for gas/liquid contacting therein, wherein the first gas/liquid contacting in the first chamber comprises co-current flow of the gas stream and scrubbing liquid, and wherein the second gas/liquid contacting in the second contacting chamber comprises countercurrent flow of the gas stream and the second scrubbing liquid through the second contacting chamber, wherein the volume of said second contacting

wherein said process additionally comprises at least one of the steps of:

chamber is smaller than the volume of said first contacting chamber,

- (a) introducing a chemical reagent for contact with the gas component to remove same from the gas stream in said gas/liquid contacting
- (b) introducing to the gas stream prior to entry thereof into the contacting chamber, a gas to enhance removal of silane from the gas stream when present therein;
- [(c) flowing the effluent gas from the contacting chamber to a second gas/liquid contacting chamber and introducing to said second contacting chamber a second scrubbing liquid for gas/liquid contacting therein, wherein the first gas/liquid contacting in the first chamber comprises cocurrent flow of the gas stream and scrubbing liquid, and wherein the second gas/liquid contacting in the second contacting chamber comprises countercurrent flow of the gas stream and the second scrubbing liquid through the second contacting chamber;]
- (c[d]) introducing an antifoam agent to scrubbing liquid for said gas/liquid contacting, to suppress foam production in the contacting chamber;
- (d[e]) suppressing deposition of calcium carbonate from scrubbing liquid containing calcium, including a step selected fro the group consisting of:
- (1) imposing a magnetic field on scrubbing liquid prior to use thereof in the contacting chamber;
 - (2) adjusting the pH of the scrubbing liquid to maintain pH thereof below 8.5;



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(3) flowing the scrubbing liquid through a lime soda ash bed prior to use of the scrubbing liquid in the contacting chamber; and

(4) precipitating the calcium content of the scrubbing liquid prior to use of the scrubbing liquid in the contacting chamber; and

(e[f]) suppressing solids formation in a passage of the scrubbing system, said passage comprising a conduit to a pressure sensing device, including a step selected from the group consisting of flowing a purge gas through the passage to suppress solids formation therein, and heating the passage to suppress solids formation therein.

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26. (Amended) A scrubbing process for treatment of an effluent gas including acid gas components and water-scrubbable components other than acid gas component, said process comprising:

sclubbing the effluent gas with <u>a neutral</u> [an] aqueous scrubbing liquid in a first scrubbing zone to remove the acid gas components of the effluent gas, with co-current flow contacting of the aqueous scrubbing liquid and effluent gas with one another to yield effluent gas reduced in acid gas components;

scrubbing the effluent gas with a second aqueous scrubbing liquid in a second scrubbing zone to remove water-scrubbable components other than acid gas component from the effluent gas, with counter -current flow contacting of the second aqueous scrubbing liquid and effluent gas with one another to yield effluent gas reduced in acid gas components and water-scrubbable components other than acid gas components wherein the volume of said second scrubbing zone is substantially smaller than the volume of said first scrubbing zone; and

flowing the effluent gas reduced in acid gas components from the first scrubber unit to the second scrubber unit. [{Joe Sweeney comments: Note that both acid gas components and water-scrubbable components other than acid gas components would be reduced in concentration after passing through the co-current flow contacting stage. In addition, water reactive gases would be reduced in concentration in the co-current stage. Acid gas components and water-soluble components are reduced in the co-current stage to concentrations approaching those corresponding to the respective equilibrium values of the acid gas components and water-soluble components in the aqueous scrubbing liquid.}]

27. (Amended) The process according to claim 26, wherein the <u>first scrubbing zone is a vessel</u> enclosing an interior volume containing a bed of packing medium [volume of said second scrubbing zone is substantially smaller than the volume of said first scrubbing zone].

Please add the following claims 51-66:

- The process according to claim 26 wherein the scrubbing liquid in the second scrubbing zone contains no caustic reagent.
- 52. The process according to claim 21 wherein the scrubbing liquid in the first contacting chamber is neutral water.
- 53. The process according to claim 21 wherein the first scrubbing liquid contains no caustic reagent.
- 54. The process according to claim 21 wherein the second scrubbing liquid contains no caustic reagent.
- The process according to claim 21 wherein the second contacting chamber has a smaller diameter than the first contacting chamber.
- 56. The process according to claim 26 wherein the second scrubbing zone has a smaller diameter than the first scrubbing zone.
- 57. The process according to claim 21 wherein the diameter of the second contacting chamber is about one-fifth the diameter of the first contacting chamber.
- 58. The process according to claim 26 wherein the diameter of the second scrubbing zone is about one-fifth the diameter of the first scrubbing zone.
- The process according to claim 21 wherein the second contacting chamber has a relatively substantially lower water flow rate than the first contacting chamber.
- 60. The process according to claim 26 wherein the second scrubbing zone has a relatively substantially lower water flow rate than the first scrubbing zone.





- A scrubbing process for the abatement of a gas component in a gas stream containing same, said scrubbing process comprising introducing the gas stream and a scrubbing liquid having no caustic agent therein to a gas/liquid contacting chamber having a packing material therein effecting gas/liquid contacting therein, wherein said process additionally at least one of the steps of:
- (a) introducing a chemical reagent for contact with the gas component to remove same from the gas stream in said gas/liquid contacting;
- (b) introducing to the gas stream prior to entry thereof into the contacting chamber, a gas to enhance removal of silane from the gas stream when present therein;
- (c) flowing the effluent gas from the contacting chamber to a second gas/liquid contacting chamber and introducing to said second contacting chamber a second scrubbing liquid for gas/liquid contacting therein, the first and second scrubbing liquid having no caustic therein, wherein the first gas/liquid contacting in the first chamber comprises co-current flow of the gas stream and scrubbing liquid, wherein the second gas/liquid contacting in the second contacting chamber comprises counter-current flow of the gas stream and the second scrubbing liquid through the second contacting chamber, and wherein the second scrubbing chamber has a diameter about one-fifth the diameter of the first scrubbing chamber
- (d) introducing an antifoam agent to scrubbing liquid for said gas/liquid contacting, to suppress foam production in the contacting chamber;
- (e) suppressing deposition of calcium carbonate from scrubbing liquid containing calcium, including a step selected from the group consisting of
- (1) imposing a magnetic field on scrubbing liquid prior to use thereof in the contacting chamber;
 - (2) adjusting the pH of the scrubbing liquid to maintain pH thereof below 8.5;
- (3) flowing the scrubbing liquid through a lime soda ash bed prior to use of the scrubbing liquid in the contacting chamber; and
- (4) precipitating the calcium content of the scrubbing liquid prior to use of the scrubbing liquid in the contacting chamber; and
- (f) suppressing solids formation in a passage of the scrubbing system, said passage comprising a conduit to a pressure sensing device, including a step selected from the group consisting of flowing a purge gas through the passage to suppress solids formation therein, and heating the passage to suppress solids formation therein.



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The process according to claim 26 further comprising introducing a chemical reagent for contact with the gas effluent component to remove same from the gas effluent in the first scrubbing zone.

- 63. The process according to claim 26 further comprising introducing a gas into the first scrubbing one to enhance removal of silane, if present.
- 64. The process according to claim 26 further comprising introducing an antifoam agent to scrubbing liquid for said gas/liquid contacting, to suppress foam production in the first and/or second scrubbing zone.
- 65. The process according to claim 26 further comprising suppressing deposition of calcium carbonate from scrubbing liquid containing calcium, including a step selected from the group consisting of:
- (1) imposing a magnetic field on scrubbing liquid prior to use thereof in the first and/or second scrubbing zone;
 - (2) adjusting the pH of the scrubbing liquid to maintain pH thereof below 8.5;
- (3) flowing the scrubbing liquid through a lime soda ash bed prior to use of the scrubbing liquid in the first and/or second scrubbing zone; and
- (4) precipitating the calcium content of the scrubbing liquid prior to use of the scrubbing liquid in the first and/or second scrubbing zone.
- 66. The process according to claim 26 further comprising suppressing solids formation in a passage of the scrubbing system, said passage comprising a conduit to a pressure sensing device, including a step selected from the group consisting of flowing a purge gas through the passage to suppress solids formation therein, and heating the passage to suppress solids formation therein.

REMARKS

In amending the claims, applicants have taken care to avoid the introduction of new matter and have used language found in the specification, in accordance with MPEP 608.01(o). Support for the subject matter and terminology of the amended claims is as follows:

